

What the invention claimed is:

1. A light diffuser fabrication method comprising the steps of:

(a) selecting the sizes of sands subject to the number of

5 light spots per inch counted subject to the size of spot light source and number of pixels of the display to be used;

(b) preparing a glass substrate and then blasting the selected sands onto the surface of the glass substrate to form a multi-frequency refracting substrate of refracting power within
10 about 1.56~1.58 under wavelength 550nm;

(c) dipping the multi-frequency refracting substrate thus obtained in polysiloxane solution in a bath at temperature within about 5°C~18°C, for enabling the multi-frequency refracting substrate to be covered with a layer of polysiloxane; and

15 (d) baking the polysiloxane coated multi-frequency refracting substrate thus obtained at 80°C for about 90 minutes, and then backing the polysiloxane coated multi-frequency refracting substrate at 125°C for about 15 minutes, causing the polysiloxane coating to be curled and formed into a layer of oxidized silicon
20 coating of chemical bond -O-Si-O-Si-O- and of refracting power within about 1.47~1.5 under wavelength 550nm on the multi-frequency refracting substrate

2. The light diffuser fabrication method comprising the

steps of:

(a) selecting the sizes of sands subject to the number of light spots per inch counted subject to the size of spot light source and number of pixels of the display to be used;

5 (b) preparing a mold having a cavity, and then sand-blasting the surface of the cavity of the mold, and then using the mold to produce a desired multi-frequency refracting substrate of refracting power within about 1.56~1.58 under wavelength 550nm;

10 (c) dipping the multi-frequency refracting substrate thus obtained in polysiloxane solution in a bath at temperature within about 5°C~18°C, for enabling the multi-frequency refracting substrate to be covered with a layer of polysiloxane; and

15 (d) baking the polysiloxane coated multi-frequency refracting substrate thus obtained at 80°C for about 90 minutes, and then backing the polysiloxane coated multi-frequency refracting substrate at 125°C for about 15 minutes, causing the polysiloxane coating to be curled and formed into a layer of oxidized silicon coating of chemical bond -O-Si-O-Si-O- and of refracting power 20 within about 1.47~1.5 under wavelength 550nm on the multi-frequency refracting substrate